



COURSE DATA

DATA SUBJECT

Code: 44420

Name: Physical nanomanufacturing techniques

Cycle: Master's Degree / Doctorate

ECTS Credits: 3

Academic year: 2026-27

STUDY (S)

Degree	Center	Acad. year	Period
2208 - Master's Degree in Molecular Nanoscience and Nanotechnology	Facultat de Química	1	First quarter

SUBJECT-MATTER

Degree	Subject-matter	Character
2208 - Master's Degree in Molecular Nanoscience and Nanotechnology	Physical nanomanufacturing techniques	COMPULSORY

COORDINATION

CORONADO MIRALLES EUGENIO

SUMMARY

The aim is that students learn basic concepts related to nanofabrication based on a bottom-up approach. Particular focus will be devoted to the possibilities and limits of the lithographic techniques, as nanofabrication tools.

PREVIOUS KNOWLEDGE

RELATIONSHIP TO OTHER SUBJECTS OF THE SAME DEGREE

There are no specified enrollment restrictions with other subjects of the curriculum.

OTHER REQUIREMENTS

Previous knowledge of chemistry, physics or materials science as taught in the degrees indicated in the recommended entry profile to the master's degree is required. Previous knowledge of molecular nanoscience and nanotechnology as taught in the Introduction Module is required.

COMPETENCES / LEARNING OUTCOMES



2208 - Master's Degree in Molecular Nanoscience and Nanotechnology

For students from field of knowledge (e.g. chemistry) to be able to scientifically communicate and interact with colleagues from another field (e.g. physics) in the resolution of problems laid out by the Molecular Nanoscience and Nanotechnology.

Students should apply acquired knowledge to solve problems in unfamiliar contexts within their field of study, including multidisciplinary scenarios.

Students should be able to integrate knowledge and address the complexity of making informed judgments based on incomplete or limited information, including reflections on the social and ethical responsibilities associated with the application of their knowledge and judgments.

Students should demonstrate self-directed learning skills for continued academic growth.

Students should possess and understand foundational knowledge that enables original thinking and research in the field.

To know the main techniques for molecular systems nanofabrication.

To know the methodological approaches used in Nanoscience.

To possess the necessary knowledge and abilities to continue with future studies in the PhD program in Nanoscience and Nanotechnology.

DESCRIPTION OF CONTENTS

1) Introduction: Lithographic techniques in the context of nanofabrication techniques.

2) Optical lithography

2.1. Basic processes and lift-off.

2.2. Thin film deposition of resists by spin-coating.

2.3. Photoresist exposition through a mask: methods and resolution; techniques for resolution improvement; Photoresists: types, examples, evaluation parameters, chemically amplified photoresists.

2.4. Holographic lithography

2.5. Limits and future of the technique.

3) Etching techniques

3.1 Wet etching techniques

3.2 Dry etching techniques: reactive ion etching (RIE) and variants, sputtering, laser ablation, etc

3.3 Clean rooms.

4) Nanolithography by nanoimprinting and microcontact.

5.1. Microcontact printing.

5.2. Nanoimprint lithography (NIL) and variants: thermal NIL, room temperature NIL, solvent-assisted NIL,



1. M4. Physical nanofabrication techniques.

1) Introduction: Lithographic techniques in the context of nanofabrication techniques.

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2.3. Photoresist exposition through a mask: methods and resolution; techniques for resolution improvement; Photoresists: types, examples, evaluation parameters, chemically amplified photoresists.

2.4. Holographic lithography

2.5. Limits and future of the technique.

step and flash NIL, etc

5.3. Molding of plastics: hot embossing, injection, etc..

5) Electron beam lithography

5.1 The scanning electron microscope

5.2 Interactions between electrons and matter

5.3 Electron beam lithography: protocols and resolution

5.4 Applications and some examples: masks and nanotransistors

6) Focused Ion Beam Lithography and other direct patterning methods

6.1 Introduction

6.2 FIB methods: sputtering, milling, deposition

6.3 Applications

7) Scanning probe lithography

7.1 The force microscope

7.2 The variety of Scanning probe lithographies

7.3 Oxidation SPL

7.4 Thermal SPL

7.5 Applications: Silicon nanowire transistors; bimolecular sensors; molecular architectures.

8) The atomic force microscope in biology and material sciences

8.1 Operational principles

8.2 AFM modes

8.3 Forces and spatial resolution

8.4 High resolution imaging of soft matter

8.5 Nanomechanical and single molecule force spectroscopies

WORKLOAD

PRESENCIAL ACTIVITIES

Activity	Hours
Tutorials	5,00
Theory	15,00
Seminar	4,00



Other activities	2,00
Total hours	26,00

NON PRESENCIAL ACTIVITIES

Activity	Hours
Attendance at other activities	0,00
Individual or group project	0,00
Independent study and work	39,00
Preparation of lessons	10,00
Resolution of case studies	0,00
Total hours	49,00

TEACHING METHODOLOGY

The classes of this subject will be taught, together with the rest of the basic module, intensively during 3 weeks in January and each year at a different university.

During the **theory classes**, the teaching staff will give an overview of the subject under study, emphasising new or particularly complex aspects. The necessary bibliographical sources will be indicated for students to study the subject in depth.

The practical classes of this subject will be devoted to the organisation of seminars in which problems related to the theoretical content will be posed and solved. Likewise, practical cases and other topics related to the subject will be discussed with the students.

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During these hours of practical activities, as far as possible, visits to laboratories and facilities related to the contents of the theoretical classes will be organised. This includes visits to device nanofabrication laboratories.

After the intensive face-to-face classes, the lecturers will ask students a series of **questions** about the contents of the course that the student will have to solve.

Professors will hold **tutorials** with the students to resolve any doubts and questions they may have. These tutorials will take place in person or remotely (email, videoconference, telephone, etc.) depending on whether the student and teacher are from the same or a different university.

Through all these activities, students will acquire the competences described in the corresponding section. The basic competences will be worked on above all during the seminars.



EVALUATION

The acquisition of the competences of the subject will be assessed by means of a written exam based on the questions posed to the students. The mark for this exam will represent 90% of the final mark for the subject.

Student participation during the training activities will represent 10% of the final grade.

In order to pass the course, it will be necessary to have attended 80% of the face-to-face training activities.

REFERENCES

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- Fundamentals of microfabrication and nanotechnology. M.J. Madou, CRC Press (2011)
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- Scanning Probe Microscopy: The lab on a tip, E. Meyer, H. Hug, R. Bennewitz, Springer (2004)
- Advanced scanning probe lithography, R. Garcia, A.W. Knoll, E. Riedo, Nature Nanotechnology 9, 577-587 (2014).
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- Controlling the emission properties of solution-processed organic distributed feedback lasers through resonator design. V. Bonal, J. A. Quintana, J. M. Villalvilla, P. G. Boj, M. A. Díaz-García; Sci. Rep., 9, 11159 (2019).
- N,N'-bis(3-methylphenyl)-N,N'-diphenylbenzidine based distributed feedback lasers with holographically fabricated polymeric resonators. V. Bonal, J.A. Quintana, J.M. Villalvilla P.G. Boj, R. Muñoz-Mármol, J.C. Mira-Martínez, M.A. Díaz-García; Polymers 13, 3843 (2021).



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